

FORM PTO-1449/A and B (Modified) INFORMATION DISCLOSURE STATEMENT BY APPLICANT				APPLICATION NO.: 10/763,819		ATTY. DOCKET NO.: H0498.70130US01	
				FILING DATE: January 23, 2004		CONFIRMATION NO.: Not yet assigned	
				APPLICANT: Tao Deng et al.			
				GROUP ART UNIT: Not yet assigned 1756		EXAMINER: Not yet assigned DUDA	
Sheet	1	of	2				

U.S. PATENT DOCUMENTS

Examiner's Initials#	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication or of issue of Cited Document MM-DD-YYY
		Number	Kind Code		
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	*A3	3,622,322	B1	Brill	11/23/71
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FORM PTO-1449/A and B (Modified) INFORMATION DISCLOSURE STATEMENT BY APPLICANT				APPLICATION NO.: 09/755,645 10/763,819	ATTY. DOCKET NO.: H0498/7130
				FILING DATE: January 5, 2001 1/23/04	
				APPLICANT: Tao Deng et al.	
				GROUP ART UNIT: Not Yet Assigned 1756	EXAMINER: Not Yet Assigned DUDA
Sheet	2	of	2		

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Examiner's Initials#	Cite No.	Foreign Patent Document			Name of Patentee or Applicant of Cited Document (not necessary)	Date of Publication of Cited Document MM-DD-YYYY	Translation (Y/N)
		Office/Country	Number	Kind Code			
ICAD	*A3	DD	153 950	A	Gesemann et al.	10.02.82	Y (Abstract)
ICAD	*A3	EP	0 057 268	A2	International Business Machines Corp.	11.08.82	
ICAD	*A3	GB	2 150 596	A	P A Consulting Services Limited	03.07.85	
ICAD	*A4	JP	04099342	A	Matshushita Electric Ind. Co. Ltd.	31.03.92	Y (Abstract)
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OTHER ART — NON PATENT LITERATURE DOCUMENTS

Examiner's Initials#	Cite No	Include name of the author (in CAPITAL LETTERS) title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, relevant page(s), volume-issue number(s), publisher, city and/or country where published.	Translation (Y/N)
ICAD	*A42	International Search Report Application No. PCT/US 01/00366 dated 03.09.01	
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	*A45	ZHANG, Y. et al., "Electroless Copper Deposition in the Photographic Gelatin Layer," <i>Journal of the Electrochemical Society</i> , 146 (4), 1270-1272, 1999	
	*A46	LIDE, D.R., "CRC Handbook of Chemistry and Physics," CRC Press, New York, 1999	
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	*A48	XU, B. et al. "Making Negative Poisson's Ratio Microstructures by Soft Lithography," <i>Adv. Materials in Press</i> 1999	
	*A49	KIRK-OTHMER Encyclopedia of Chemical Technology, 4 th Edition, 1999, p. 1541	
ICAD	A50	DENG, T., et al., "Fabrication of Metallic Microstructure Using Exposed, Developed Silver Halide-Based Photographic Film," <i>Anal Chem.</i> 2000, 72, 645-651	

EXAMINER K. Duda	DATE CONSIDERED 6-8-06
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#EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

*a copy of this reference is not provided as it was previously cited by or submitted to the office in a prior application, Serial No. 09/755,645, filed January 5, 2001, and relied upon for an earlier filing date under 35 U.S.C. 120 (continuation, continuation-in-part, and divisional applications).